

Defects in an orthorhombic MoAlB MAB phase thin film grown at moderate synthesis temperature

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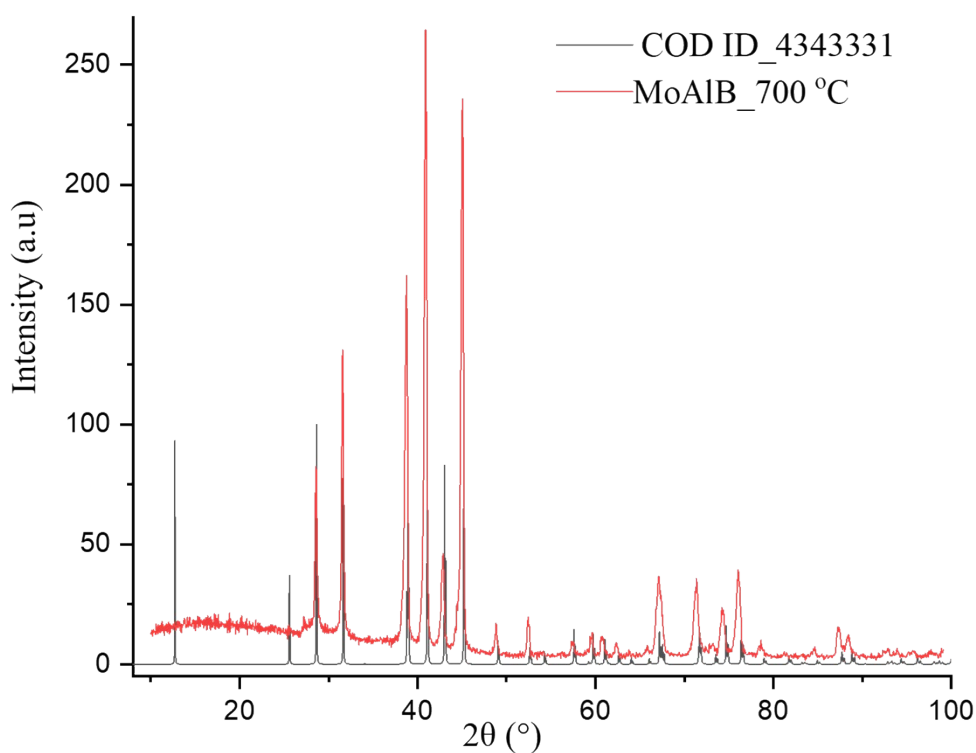


Fig. S1: X-ray diffraction data of the MoAlB film grown by DC magnetron sputtering. Reference pattern and reference card number are taken from Crystallography Open Database [1].

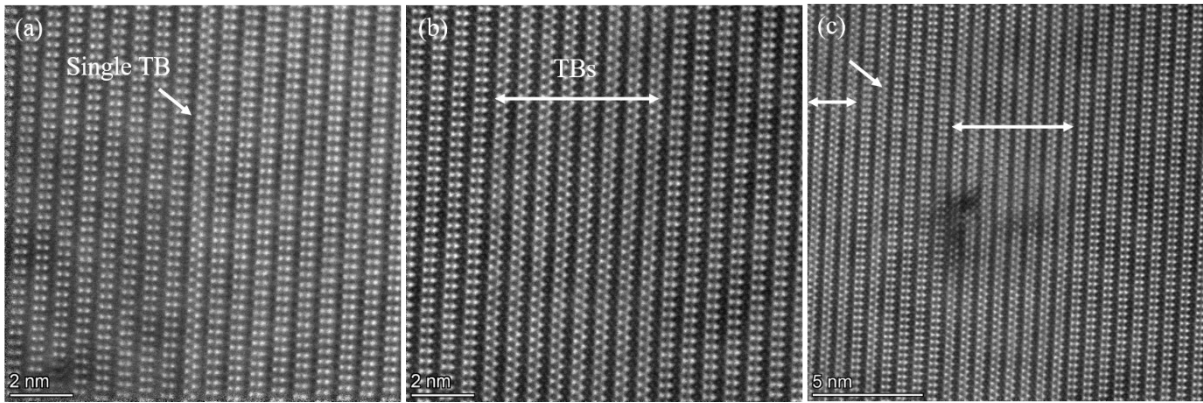


Fig. S2: High resolution HAADF STEM micrographs in (a)-(c) represent single-unit wide (white arrow) to several-nanometer-wide twin domains (double headed arrows) within different grains.

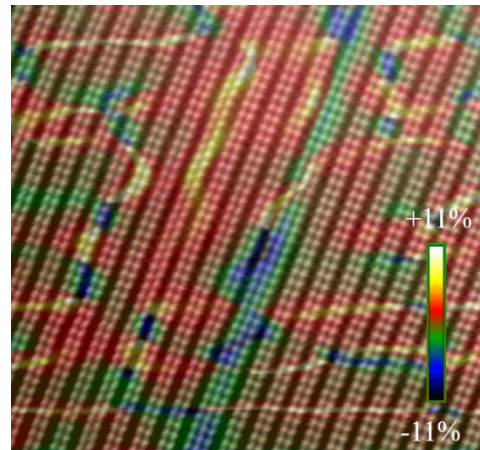


Fig. S3: Local phase map showing relative interplanar differences along ϵ_{yy} .

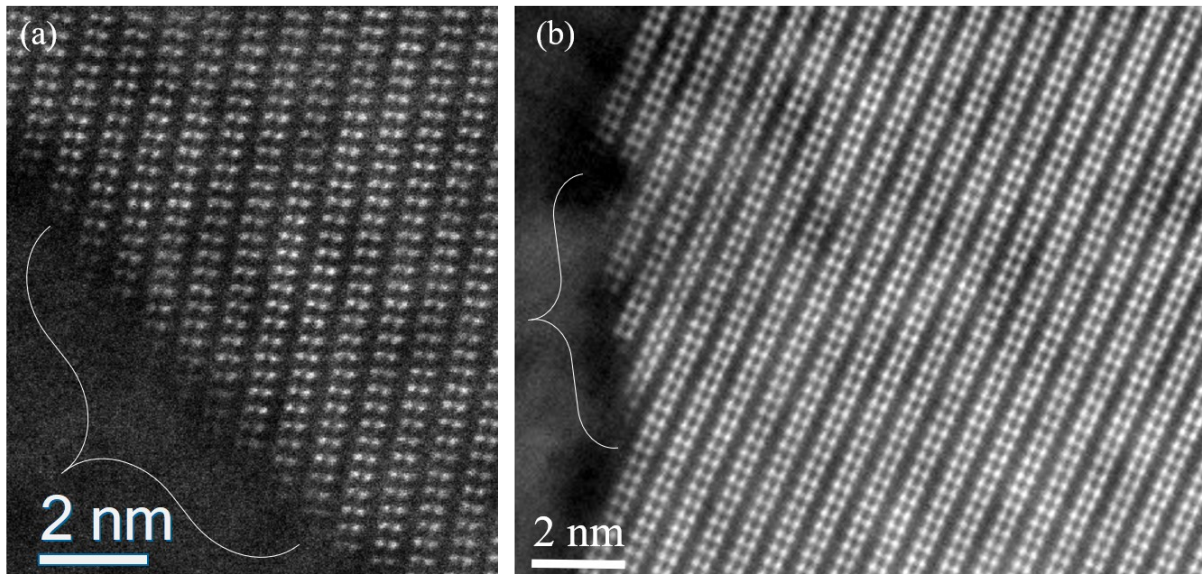


Fig. S4: HAADF STEM micrographs showing faceted grain boundaries from two different areas (a) and (b).

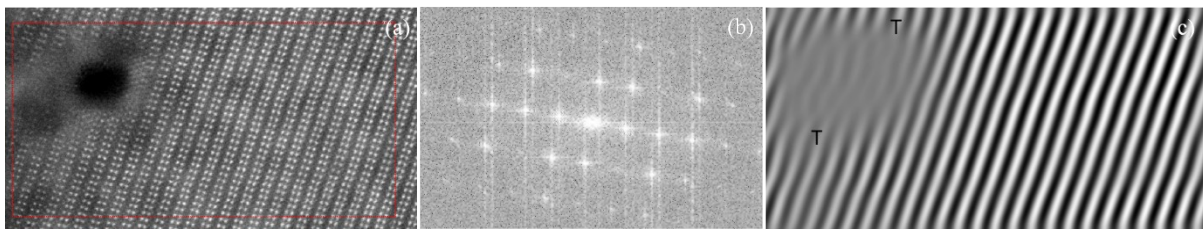


Fig. S5: Inverse fast Fourier transformation (IFFT) of area (a) is performed using FFT image in (b). (c) Lattice fringes over the 3D amorphous region show a discontinuity.

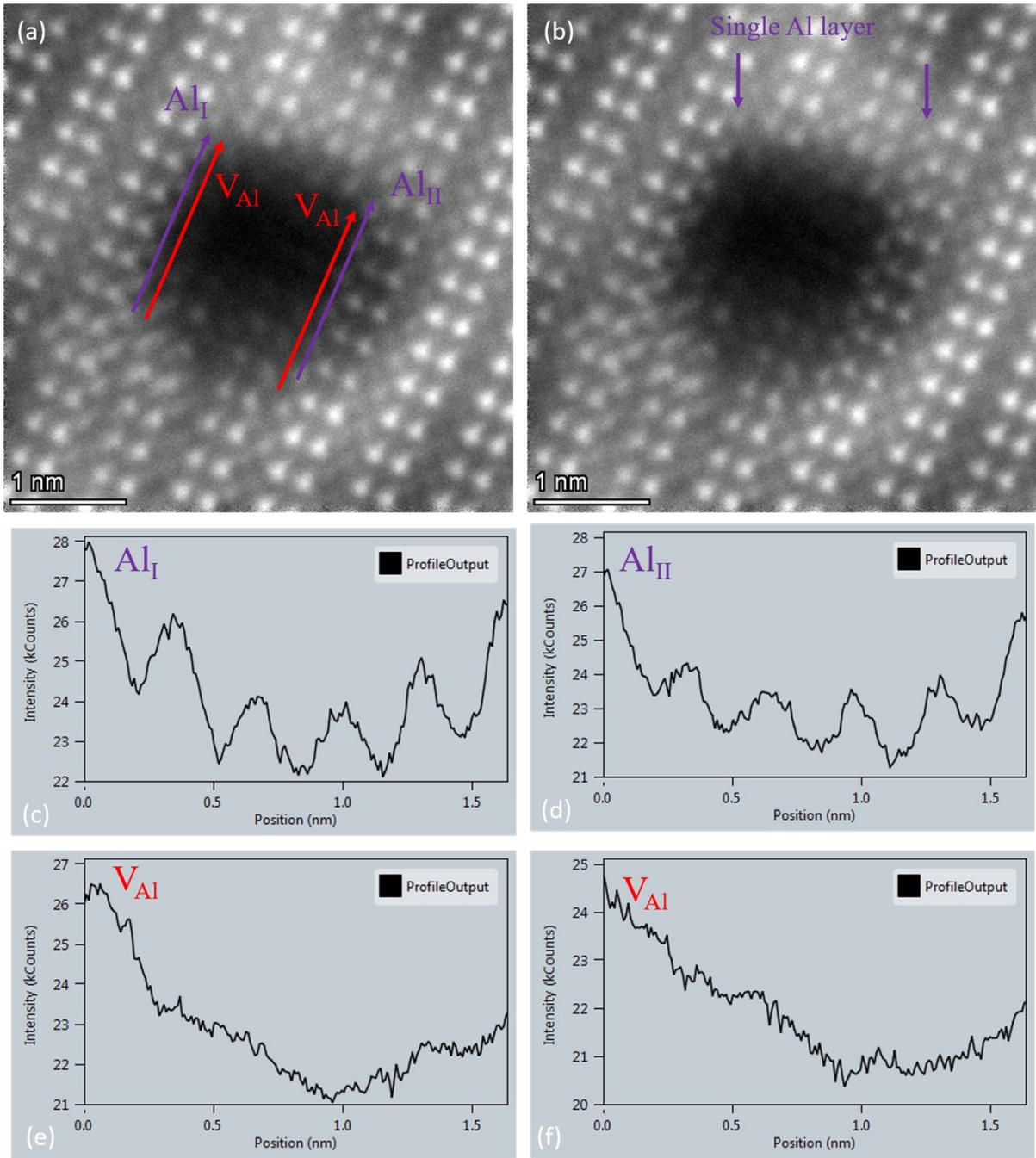


Fig. S6: (a) Presence of single-layer Al at the vicinity of the 3D cluster is denoted by Al_I and Al_{II} and the vacant columns are marked by V_{Al}. Corresponding line profile are drawn in (c)-(f). Al atoms in single layer are indicated by violet arrows in the HAADF STEM micrographs (b).

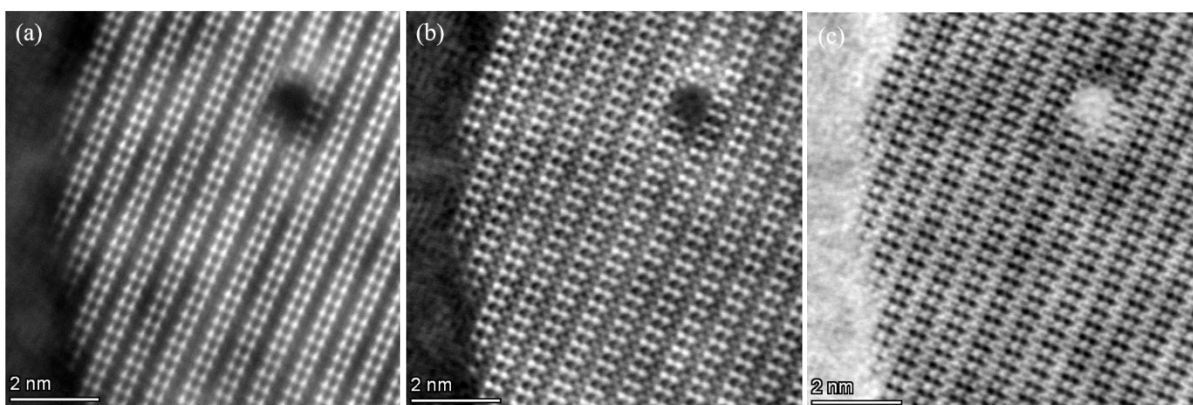


Fig. S7: Simultaneously acquired (a) HAADF, (b) ADF and (c) ABF STEM images of the grain boundary are shown here.

References

1. M. Ade and H. Hillebrecht, Ternary Borides Cr_2AlB_2 , Cr_3AlB_4 , and Cr_4AlB_6 : The First Members of the Series $(\text{CrB}_2)_n\text{CrAl}$ with $n = 1, 2, 3$ and a Unifying Concept for Ternary Borides as MAB-Phases, *Inorg. Chem.*, 2015, **54**(13), 6122-6135.